

## **SU-8 2000.5 – run sheet**

Kayaku Advanced Materials

[nanyte.com/photoresists/su-8-2000-5](http://nanyte.com/photoresists/su-8-2000-5) · last updated 2026-09-13

**Thickness:** 0.5–0.8  $\mu\text{m}$

**Softbake:** 95 °C · hotplate

**Exposure dose** – dose by film thickness

| <b>Film thickness</b> | <b>Dose</b> |
|-----------------------|-------------|
|-----------------------|-------------|

|                     |                                |
|---------------------|--------------------------------|
| 0.5–2 $\mu\text{m}$ | 60–180 $\text{mJ}/\text{cm}^2$ |
|---------------------|--------------------------------|

|                   |                                |
|-------------------|--------------------------------|
| 3–5 $\mu\text{m}$ | 90–105 $\text{mJ}/\text{cm}^2$ |
|-------------------|--------------------------------|

|                    |                                 |
|--------------------|---------------------------------|
| 6–15 $\mu\text{m}$ | 110–140 $\text{mJ}/\text{cm}^2$ |
|--------------------|---------------------------------|

|                     |                                 |
|---------------------|---------------------------------|
| 16–25 $\mu\text{m}$ | 140–150 $\text{mJ}/\text{cm}^2$ |
|---------------------|---------------------------------|

|                     |                                 |
|---------------------|---------------------------------|
| 26–40 $\mu\text{m}$ | 150–160 $\text{mJ}/\text{cm}^2$ |
|---------------------|---------------------------------|

**Post-exposure bake:** 95 °C · hotplate

**Develop:** Developer SU-8 Developer; ethyl lactate or diacetone alcohol may also be used · Rinse Spray and wash the developed image with fresh SU-8 developer for about 10 s, then air-dry with filtered pressurised air or nitrogen. · Method immersion, spray or spray-puddle

**Hardbake:** 150–250 °C · 5–30 min